Ultra-stable Laser system for Photocathode RF gun Applications

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Contents

- ProductionPulrise
- Research & Development Amplifier Square pulse

Pulrise: Stable UV Laser for Photoinjector



Laser medium Nd:YLF

Pulse width 12 ps @1047 nm, 8 ps @262 nm

Pulse energy 2 mJ @ 1047 nm, 0.2 mJ @ 262 nm

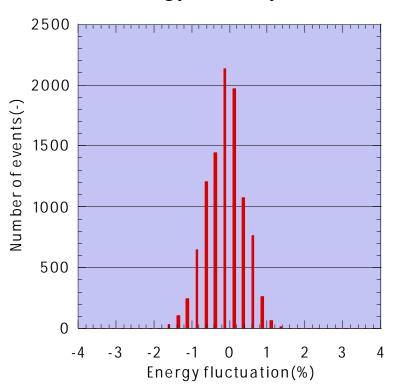
Jitter <0.5 ps RMS

Dimension 600 mm(W)X900mm(D)X300mm(H)

Repetition rate 25 Hz (100 Hz available)

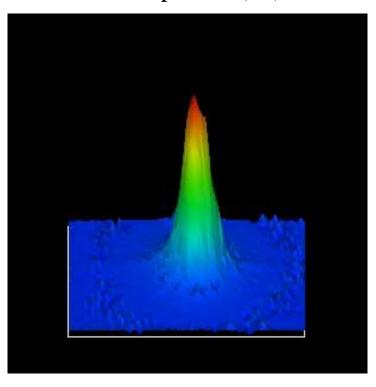
Stability of Pulrise

Energy stability (IR)



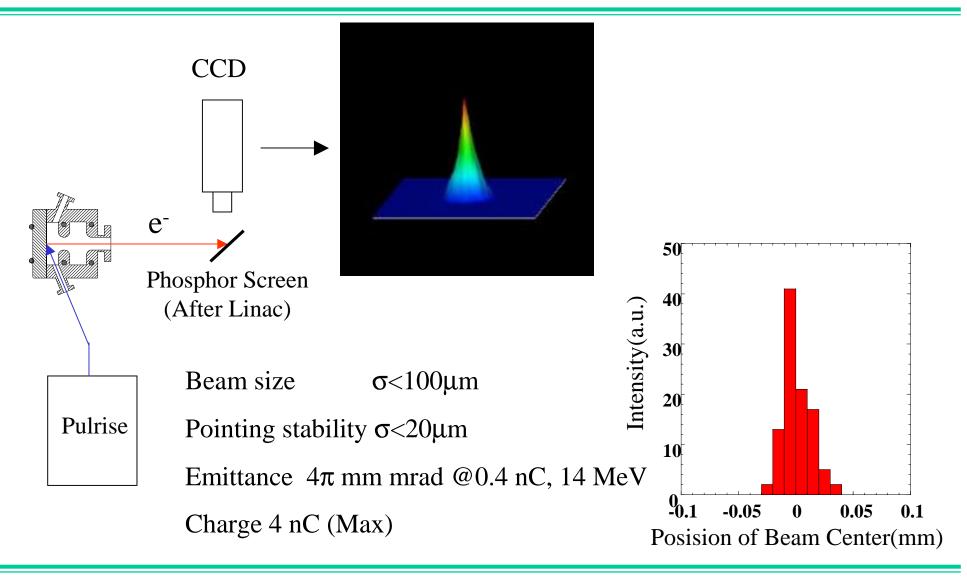
Total shot number 10000 Standard deviation 0.55%

Beam profile (IR)

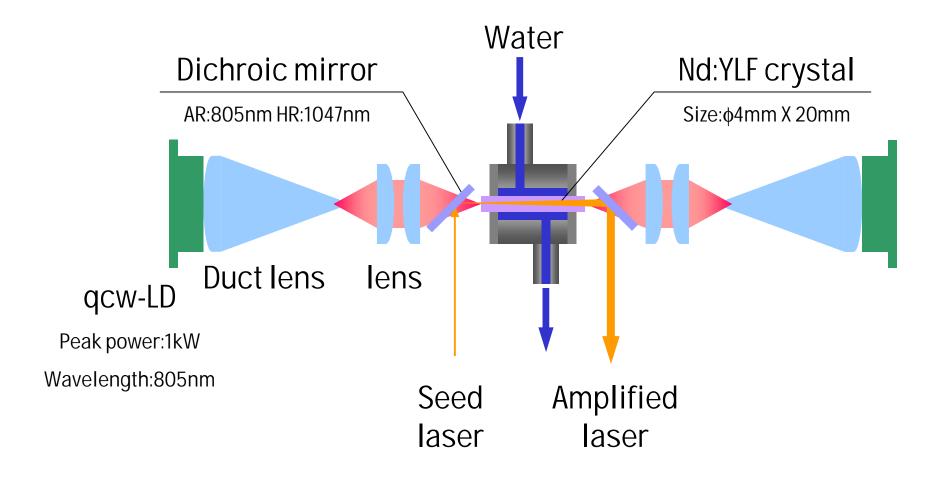


Pointing stability $\sigma=5\mu$ rad

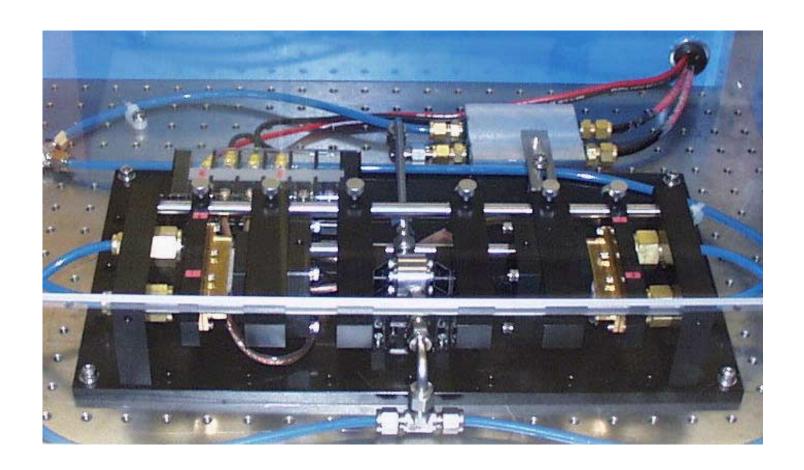
Electron Bunch Characteristics



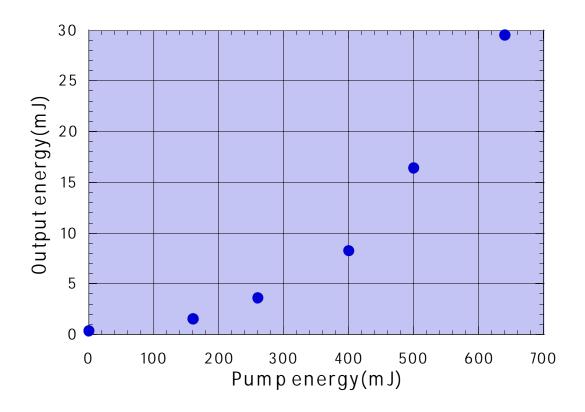
Nd:YLF Amplifier



Nd:YLF Amplifier

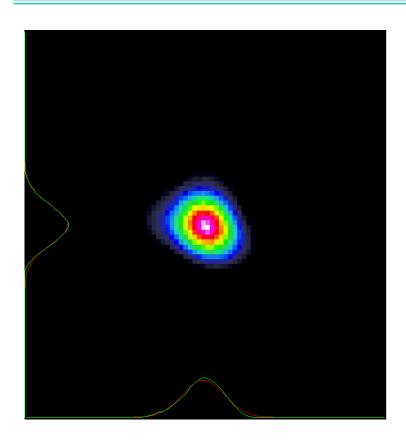


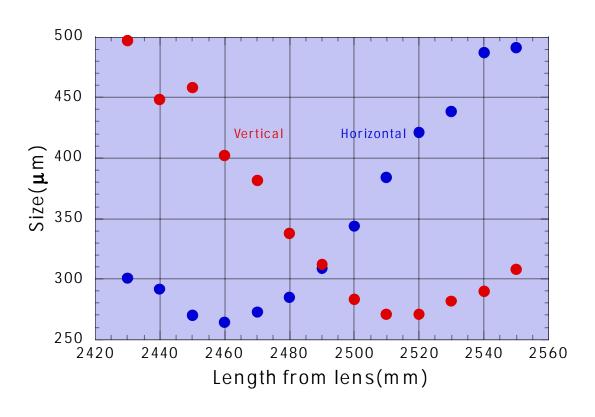
Amplification with 2-pass configuration



The amplifier was operated as double pass configuration. The seed laser energy was 0.4mJ. The pump laser pulse width was $400\mu s$ and the repetition rate was 10Hz.

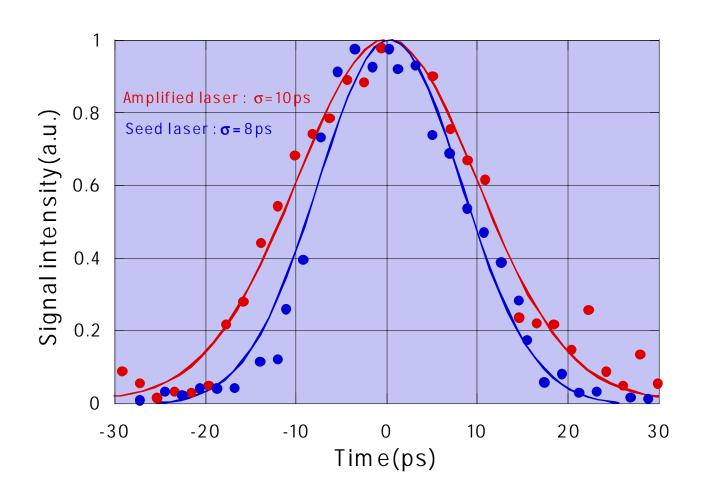
Beam Profile and Focused Diameter



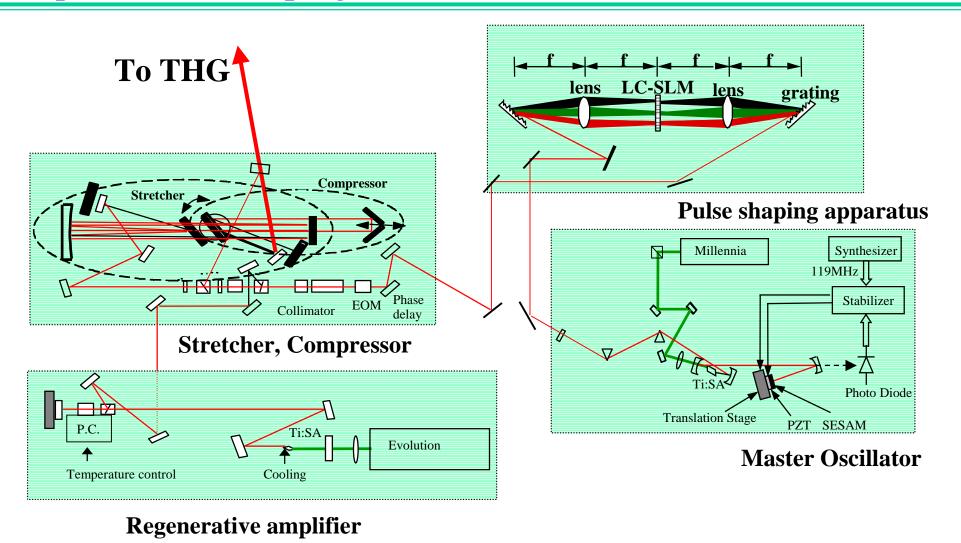


with 2500 mm lens

The beam diameter (the width of the 1/e^2 intensity level) was approximately 300µm.

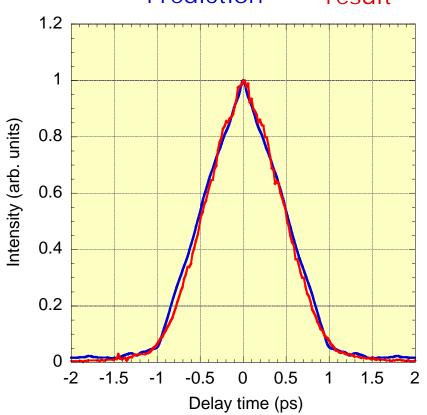


Square Pulse Shaping with a SLM



Autocorrelation Trace





Pulsewidth 1 ps Energy 0.3mJ (IR) repetition 1 kHz

Triangle trace indicates square temporal profile.

Summery

Pulrise

Stable UV laser for photo-injector Already open to the market

Amplifier

Prototype model finished Continuing for production model

> Please visit Photonics West at San Jose Paper #4267-30

> Poster session 5:30 to 7:00 PM on 1/24

Square Pulse Trying to generate THG

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